

NAVOLCHI

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TU / **e**

Technische Universiteit
Eindhoven
University of Technology

Where innovation starts

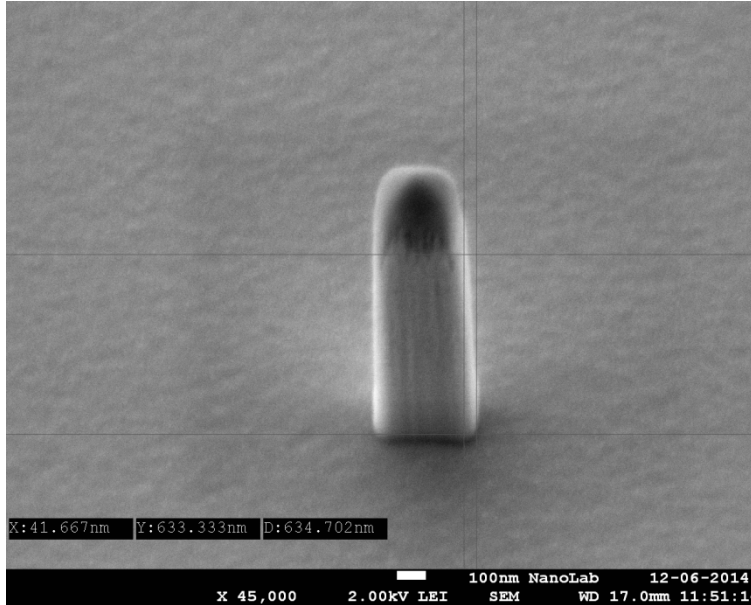
Milestones and Deliverables

MS40	Individual plasmonic devices characterization, testing and evaluation	WP 6	TU/e	04/2014
D6.1	Report on characterization results of all plasmonic devices	WP 6	TU/e	01/2014

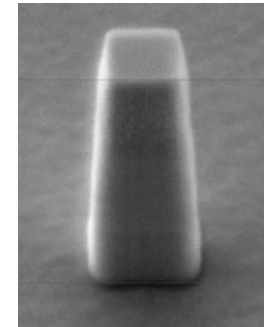
→ Delay due to lack of results

Etching recipe Improvement by RF power

- Vertical etching: less than 1 degree!

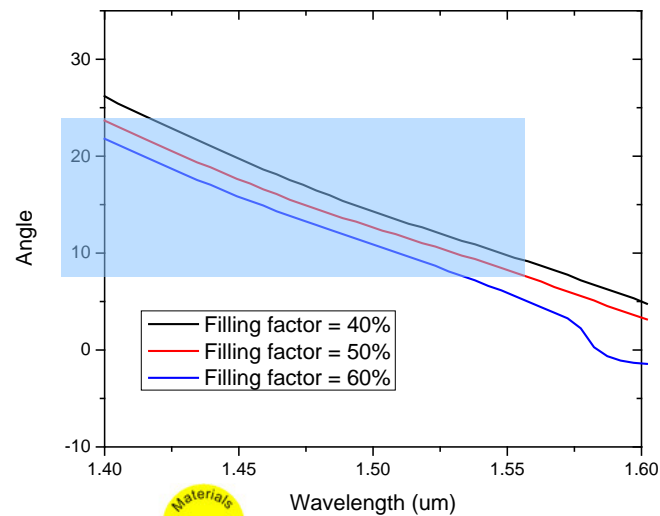
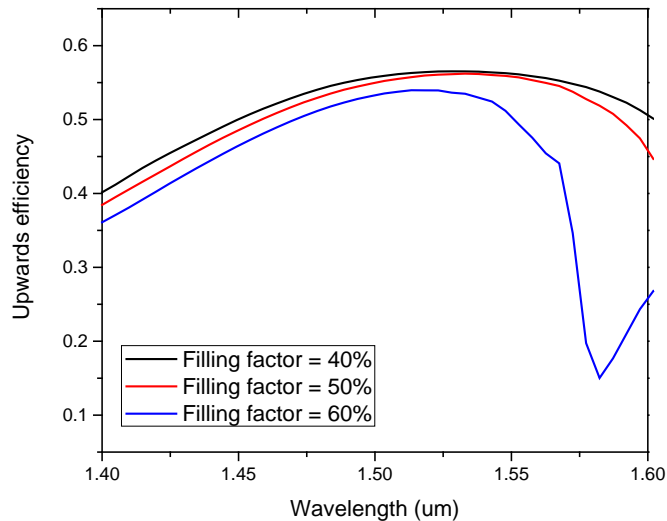
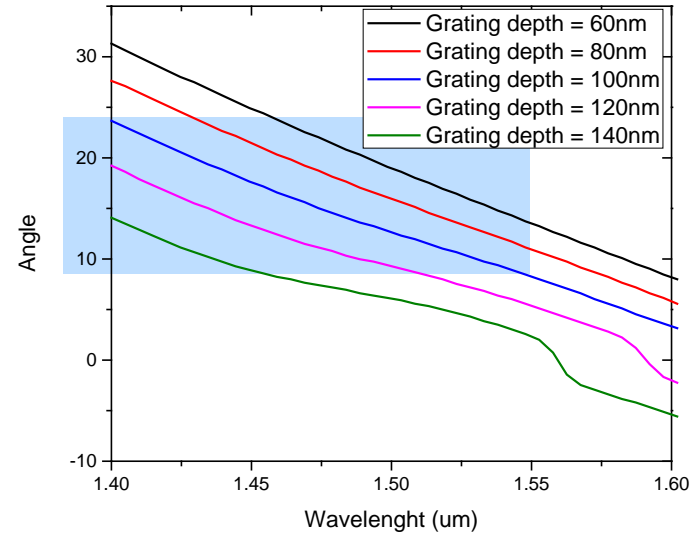
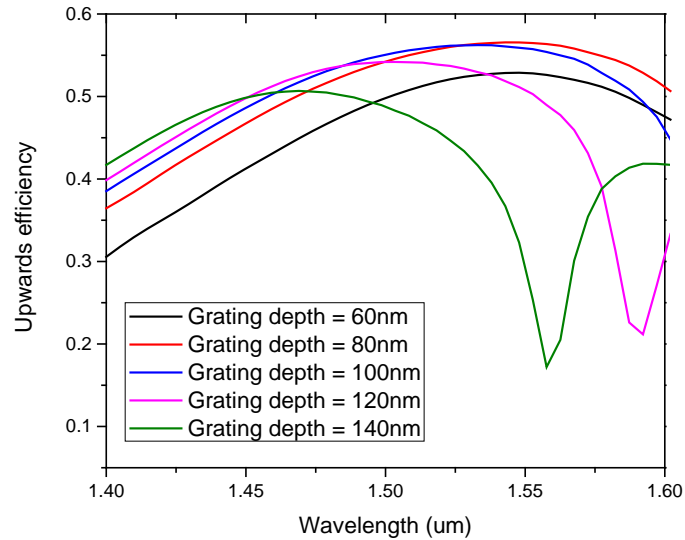


Normal recipe:



- Next: achieve etching with thick hard mask

Re-optimization of grating coupler for free-space coupling with high NA lens (~25° max)



- Dissemination:
 - Talk at IPR: Efficient metal grating coupler for membrane-based integrated photonics, V. Dolores Calzadilla, A. Higuera-Rodriguez, D. Heiss, M. Smit, Oral participation, IPR 2014.
- Main bottleneck in our clean room at the moment: EBL is often down